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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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| Appl. No. | 10/003,908 | Confirmation No. | 7739 |
| First Inventor | William R. Entley | Filing Date | 11/1/2001 |
| Tech. Center/ Art Unit | 1765 | Examiner | Anita Karen Alanko |
| Title: | In Situ Plasma Process To Remove Fluorine Residues From The Interior Surfaces Of A CVD Reactor | | |
| Docket No.: | NVS013 US | Customer No.: | 34036 |

Santa Clara, California
October 19, 2004

MAIL STOP AF
COMMISSIONER FOR PATENTS
P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT AFTER FINAL ACTION

Dear Sir:

In response to the Advisory Action dated August 25, 2004, please amend the above-identified application as follows.

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 6 of this paper.